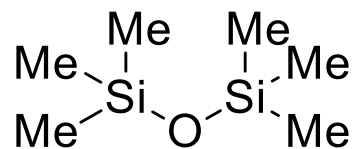


Catalog # 14-7125 Hexamethyldisiloxane, 97+% HMDSO



Technical Notes

1. Organosilicon precursor used in the plasma-enhanced chemical vapour deposition (PECVD) process of super hydrophobic C-rich polymeric (silicone-like, SiC_xHyO_z) and doped semiconducting SiO_x films and coatings [1-7].

References:

1. *Appl. Surf. Sci.*, **2010**, 256, 2509
2. *J. Phys. Chem. C*, **2011**, 115, 22225
3. *Appl. Surf. Sci.*, **2011**, 257, 3786
4. *RSC Adv.*, **2014**, 4, 45442
5. *Thin Solid Films*, **2015**, 590, 299
6. *Surf. Coat. Tech.*, **2016**, 225
7. *Nanomaterials*, **2018**, 8, 530